

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|-------|--|----------------------------------|------------------|---------|---------------------|
| L1 | 1 | "20020025408" | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 16:07 |
| L2 | 1628 | ((977/887) or (264/293)).CCLS. | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 16:43 |
| S1 | 20854 | (nanoimprint\$4 step near3 flash near3 \$5imprint\$4) and (photoresist resist) with temperature\$2 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 12:51 |
| S2 | 164 | (nanoimprint\$4 step near3 flash near3 \$5imprint\$4) and (photoresist resist) with temperature\$2 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 12:52 |
| S3 | 126 | (nanoimprint\$4 step near3 flash near3 \$5imprint\$4) and (photoresist resist) with heat\$4 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:05 |
| S4 | 28 | (step near3 flash near3 \$5imprint\$4) and (photoresist resist) with heat\$4 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:05 |
| S5 | 10 | (step near3 flash near3 \$5imprint\$4) and (photoresist resist) same heat\$4 with (uv "u.v." ultraviolet) | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:06 |
| S6 | 2201 | (photoresist resist) same heat\$4 with (uv "u.v." ultraviolet) | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:07 |
| S7 | 166 | (photoresist resist) same heat\$4 with flow \$4 same (uv "u.v." ultraviolet) | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:07 |

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|-----|------|--|----------------------------------|----|-----|---------------------|
| S8 | 1019 | (photoresist resist) same (bake baking baked) with during with (exposing exposed exposure expose) | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:11 |
| S9 | 51 | (photoresist resist) same (bake baking baked) with during with (exposing exposed exposure expose) with (uv "u.v." ultraviolet) | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:11 |
| S10 | 208 | (photoresist resist) same (bake baking baked heat\$4) same (uv "u.v." ultraviolet) and contact adj mask \$2 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:17 |
| S11 | 96 | (photoresist resist) same (heat\$4) same (uv "u.v." ultraviolet) and contact adj mask \$2 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:19 |
| S12 | 29 | (photoresist resist) same (heat\$4) same (uv "u.v." ultraviolet) same contact adj mask \$2 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:19 |
| S13 | 5 | (photoresist resist) same (heat\$4) with contact adj mask\$2 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:20 |
| S14 | 1 | 10/659006 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:32 |
| S15 | 49 | (bailey and choi).in. | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:35 |
| S16 | 27 | (sfil step near3 flash\$4 near3 \$5imprint) and (photoresist resist) with heat\$4 | US- PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:38 |

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|-----|------|---|------------------------------|----|-----|---------------------|
| S17 | 9 | 10/081199 | US-PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 13:42 |
| S18 | 288 | nanoimprint\$4 same (uv ultraviolet "u.v.") | US-PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 14:16 |
| S19 | 940 | nanoimprint\$4 and (uv ultraviolet "u.v.") | US-PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 14:17 |
| S20 | 1769 | imprint adj lithography and (uv ultraviolet "u. v.") | US-PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 14:19 |
| S21 | 236 | imprint adj lithography with (uv ultraviolet "u. v.") | US-PGPUB; USPAT; USOCR | OR | OFF | 2009/01/18 14:19 |

1/18/2009 4:44:55 PM